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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/659,828	09/11/2003	David R. Hembree	99-0812.2	5963
22823	7590 06/17/2004		EXAMINER	
STEPHEN A	- ·	LUU, CHUONG A		
THE LAW OFFICE OF STEVE GRATTON 2764 SOUTH BRAUN WAY LAKEWOOD, CO 80228			ART UNIT	PAPER NUMBER
			2825	
			DATE MAILED: 06/17/2004	4

Please find below and/or attached an Office communication concerning this application or proceeding.

		Applicati n N .	Applicant(s)				
		10/659,828	HEMBREE ET AL.				
	Office Action Summary	Examin r	Art Unit				
		Chuong A Luu	2825				
Period fe	The MAILING DATE of this communic or Reply	ation appears on the cover sh	eet with the corresp ndence add	ress			
A SH THE - Exte after - If th - If NO - Failt Any	IORTENED STATUTORY PERIOD FO MAILING DATE OF THIS COMMUNIC ensions of time may be available under the provisions of SIX (6) MONTHS from the mailing date of this communic e period for reply specified above is less than thirty (30) D period for reply is specified above, the maximum statu ure to reply within the set or extended period for reply w reply received by the Office later than three months afte led patent term adjustment. See 37 CFR 1.704(b).	CATION.  f 37 CFR 1.136(a). In no event, however, nication.  days, a reply within the statutory minimulatory period will apply and will expire SIX ill, by statute, cause the application to be	may a reply be timely filed  m of thirty (30) days will be considered timely. (6) MONTHS from the mailing date of this comcome ABANDONED (35 U.S.C. § 133).	munication.			
Status							
1)	Responsive to communication(s) filed	on					
		b) This action is non-final.					
′=		•	I matters, prosecution as to the r	nerits is			
-/	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Disposit	ion of Claims						
·		nnlication					
7/23	<ul> <li>✓ Claim(s) 47-67 is/are pending in the application.</li> <li>4a) Of the above claim(s) is/are withdrawn from consideration.</li> </ul>						
5)□	Claim(s) is/are allowed						
· <u> </u>	☐ Claim(s) is/are allowed.  ☐ Claim(s) <u>47-67</u> is/are rejected.						
	7) Claim(s) is/are rejected.  7) Claim(s) is/are objected to.  8) Claim(s) are subject to restriction and/or election requirement.						
·							
Applicat	ion Papers						
	•	Evenines					
9) The specification is objected to by the Examiner.							
10)[	10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.						
	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
11)□	Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).  11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.						
		by the Examiner. Note the att	adrica dinoc Addon di Tomi 1 10	- 1 <b>02.</b>			
_	under 35 U.S.C. § 119						
	Acknowledgment is made of a claim for All b) Some * c) None of:  1. Certified copies of the priority do 2. Certified copies of the priority do 3. Copies of the certified copies of application from the International	ocuments have been receive ocuments have been receive the priority documents have	d. d in Application No been received in this National St	tage			
* 8	See the attached detailed Office action	` ` ' '					
Attachmen		_					
1) ⊠ Notic 2) □ Notic	e of References Cited (PTO-892) to of Draftsperson's Patent Drawing Review (PTO	4) Inte	rview Summary (PTO-413) er No(s)/Mail Date				
3) 🔯 Infon	te of Dransperson's Patent Drawing Review (P10 mation Disclosure Statement(s) (PTO-1449 or P <sup>-1</sup> r No(s)/Mail Date <u>10/6/03; 11/17/03</u> .		ice of Informal Patent Application (PTO-1	52)			

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#### **DETAILED ACTION**

### **Drawings**

The drawings are objected to under 37 CFR 1.83(a). The drawings must show every feature of the invention specified in the claims. Therefore, the limitation of "a plurality" must be shown or the feature(s) canceled from the claim(s). No new matter should be entered.

A proposed drawing correction or corrected drawings are required in reply to the Office action to avoid abandonment of the application. The objection to the drawings will not be held in abeyance.

#### **PRIOR ART REJECTIONS**

#### **Statutory Basis**

## Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claim Rejections - 35 USC § 103

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The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

## The Rejections

Claims 47-67 are rejected under 35 U.S.C. 102(e) as being anticipated by Gilleo et al. (U.S. 6,204,455 B1).

Gilleo discloses a microelectronic element assembly with

(47) a semiconductor die (42) comprising a plurality die contacts (44) in a pattern;

a plurality of conductors (20) on the die (42) in electrical communication with the die contacts (44) configured redistribute the pattern of the die contacts (44);

a plurality of first contacts (44) on the die (42) in electrical communication with the conductors (20);

a plurality of second contacts on the die in electrical communication with the conductors (20) configured for electrical contact a test probe without electrical engagement of the first contacts (44) (see Figure 2);

- (48) wherein the first contacts comprise bumps in an area array (see column 6, lines 35-38);
- (49) further comprising an under bump metallization layer on each first contact (see Figure 2);
  - (50) wherein the second contacts comprise pads (see Figure 2);

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(51) wherein the component is contained on a wafer (see column 12, line 3);

- (52) further comprising an electrically insulating layer between the die and the conductors (see Figure 2);
- (53) wherein conductors are configured to fan out or to fan in the pattern of the die contacts (see Figure 2);
- (54) a semiconductor die having a face and a plurality of die contacts on the face in a pattern (see Figure 2);

a plurality of conductors on the face in electrical communication vith the die contacts configured redistribute the pattern of the die contacts (see Figure 2);

an electrically insulating layer on the conductors having a plurality of openings;

a plurality of first contacts on the face in electrical communication with the conductors (see Figure 2);

a plurality second contacts on the face in electrical communication with the conductors comprising pads aligned with the openings configured for electrical contact with a test probe (see column 2, lines 49-54. Figure 2);

- (55) wherein the pads comprise portions of the conductors (see Figure 2);
- (56) wherein the component comprises a semiconductor wafer;
- (57) wherein the first contacts comprise balls in a ball grid array and each ball of the ball grid array is in electrical communication with a second contact (see Figure 2);
  - (58) a semiconductor wafer;

a plurality of components on the wafer comprising a plurality of die contacts;

a redistribution circuit on the wafer comprising a plurality of conductors in electrical communication with the die contacts;

a plurality test contacts on the wafer electrical communication with the conductors;

a plurality of terminal contacts on the wafer electrical communication with the conductors;

the test contacts configured for electrical contact by a test probe without interference from the terminal contacts, each test contact electrical communication with a terminal contact (see Figure 2);

- (59) wherein the terminal contacts comprise under bump metallization layers and solder bumps (see Figure 2);
- (60) further comprising an electrically insulating layer on the redistribution circuit having a plurality of openings aligned with the test contacts (see Figure 2);
- (61) wherein the test contacts comprise portions of the conductors (see Figure 2);
- (62) wherein the test probe comprises a needle probe, a buckle beam probe, a spring segment probe or a silicon probe;
  - (63) a semiconductor die comprising a plurality of die contacts in a pattern;
- a plurality of redistribution conductors on the die in electrical communication with the die contacts (see Figure 2);
- a plurality of bumped contacts on the die in electrical communication with the conductors;

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a plurality of test contacts on the die electrical communication with the conductors, each test contact configured for electrical contact by a test probe without interference from the bumped contacts (see Figure 2);

- (64) wherein the die is contained on a semiconductor wafer containing a plurality of dice substantially similar to the die (see Figure 2);
- (65) wherein the bumped contacts comprise solder balls and under bump metallization layers in a grid array;
- (66) wherein the test contacts comprise portions of the redistribution conductors (see Figure 2);
  - (67) wherein the test contacts comprise separate pads (see Figure 2).

Claims 47-67 are rejected under 35 U.S.C. 102(b) as being anticipated by Sumi et al. (U.S. 5,767,528).

Sumi discloses a semiconductor device with

(47) a semiconductor die (11) comprising a plurality die contacts (16) in a pattern; a plurality of conductors (20) on the die (42) in electrical communication with the die contacts (16) configured redistribute the pattern of the die contacts (16);

a plurality of first contacts (16) on the die (11) in electrical communication with the conductors (20);

a plurality of second contacts (14) on the die (11) in electrical communication with the conductors (20) configured for electrical contact a test probe without electrical engagement of the first contacts (16) (see Figure 3);

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(48) wherein the first contacts comprise bumps in an area array (see Figure 3);

- (49) further comprising an under bump metallization layer on each first contact (see Figure 3);
  - (50) wherein the second contacts comprise pads (see Figure 3);
  - (51) wherein the component is contained on a wafer (see column 12, line 3);
- (52) further comprising an electrically insulating layer between the die and the conductors (see Figure 3);
- (53) wherein conductors are configured to fan out or to fan in the pattern of the die contacts (see Figure 3);
- (54) a semiconductor die having a face and a plurality of die contacts on the face in a pattern (see Figure 3);

a plurality of conductors on the face in electrical communication with the die contacts configured redistribute the pattern of the die contacts (see Figure 3);

an electrically insulating layer on the conductors having a plurality of openings;

a plurality of first contacts on the face in electrical communication with the conductors (see Figure 3);

a plurality second contacts on the face in electrical communication with the conductors comprising pads aligned with the openings configured for electrical contact with a test probe (see column 9, lines 12-53. Figure 3);

- (55) wherein the pads comprise portions of the conductors (see Figure 3);
- (56) wherein the component comprises a semiconductor wafer (see column 9, lines 46-47);

(57) wherein the first contacts comprise balls in a ball grid array and each ball of the ball grid array is in electrical communication with a second contact (see Figure 3);

(58) a semiconductor wafer;

a plurality of components on the wafer comprising a plurality of die contacts;

a redistribution circuit on the wafer comprising a plurality of conductors in electrical communication with the die contacts;

a plurality test contacts on the wafer electrical communication with the conductors;

a plurality of terminal contacts on the wafer electrical communication with the conductors;

the test contacts configured for electrical contact by a test probe without interference from the terminal contacts, each test contact electrical communication with a terminal contact (see column 9, lines 12-53. Figure 3);

- (59) wherein the terminal contacts comprise under bump metallization layers and solder bumps (see Figure 3);
- (60) further comprising an electrically insulating layer on the redistribution circuit having a plurality of openings aligned with the test contacts (see Figure 3);
- (61) wherein the test contacts comprise portions of the conductors (see Figure 3);
- (62) wherein the test probe comprises a needle probe (see column 5, lines 24-28);
  - (63) a semiconductor die comprising a plurality of die contacts in a pattern;

a plurality of redistribution conductors on the die in electrical communication with the die contacts (see Figure 3);

a plurality of bumped contacts on the die in electrical communication with the conductors;

a plurality of test contacts on the die electrical communication with the conductors, each test contact configured for electrical contact by a test probe without interference from the bumped contacts (see column 9, lines 12-53. Figure 3);

- (64) wherein the die is contained on a semiconductor wafer containing a plurality of dice substantially similar to the die (see Figure 3);
- (65) wherein the bumped contacts comprise solder balls and under bump metallization layers in a grid array (see Figure 3);
- (66) wherein the test contacts comprise portions of the redistribution conductors (see Figure 3);
  - (67) wherein the test contacts comprise separate pads (see Figure 3).

## Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Chuong A Luu whose telephone number is (571) 272-1902. The examiner can normally be reached on M-F (6:30-3:00).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew Smith can be reached on (571) 272-1907. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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June 3, 2004

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